

Abstract

Disclosed are a new class of compounds useful as liquid for immersion lithography, which liquid contains molecules so that the liquid is substantially transparent at a wavelength used for said liquid immersion lithography, and has a degree of polarization of light, which is incident on a sample of the liquid in a forward direction and which is scattered in a direction perpendicular to the forward direction within a plane of scattering defined by the forward direction and the direction perpendicular to the forward direction, is larger than 0.9; and methods for exposing a photoresist layer on a semiconductor substrate for producing microelectronic circuits or micro-electromechanical systems (MEMS), which method uses a step of liquid immersion lithography with a liquid of the invention.